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PPLICATION NO	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO	CONFIRMATION NO
09 773,798	02/01/2001	Douglas Duane Coolbaugh	BUR920000143US1(13890)	8546
	590 05 03 2002			
Richard L. Catania, Esq.			EXAMINER.	
Scully, Scott, Murphy & Presser 400 Garden City Plaza Garden City, NY 11530			FARAHANI, DANA	
			ART UNIT	PAPER NUMBER
			2814	
			DATE MAILED: 05-03-2002	

Please find below and or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)
Office Action Summary		09/773.798	COOLBAUGH ET AL
		Examiner	Art Unit
		; Dana Farahani	2814
Period fo	The MAILING DATE of this communication a or Reply	ppears on the cover sheet w	with the correspondence address
A SHI THE I - Exter after - If the - If NO - Failu - Any r	ORTENED STATUTORY PERIOD FOR REF MAILING DATE OF THIS COMMUNICATION asions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication period for reply specified above is less than thirty (30) days a reperiod for reply is specified above, the maximum statutory perior to reply within the set or extended period for reply will by state eply received by the Office later than three months after the mailed patent term adjustment. See 37 CFR 1 704(b)	1 136(a) In no event however may a eply within the statutory minimum of the dwill apply and will expire SIX (6) MO utel cause the application to become A	a reply be timely filed  iirty (30) days will be considered timely  DNTHS from the mailing date of this communication  ABANDONED (35 U S C § 133)
1)[	Responsive to communication(s) filed on M	larch 19 2002 .	
2a)□		This action is non-final.	
3)	Since this application is in condition for allo closed in accordance with the practice unde	•	,
Dispositi	on of Claims		
4)[	Claim(s) 1-17 is/are pending in the applicati	on.	
	4a) Of the above claim(s) is/are withdo	rawn from consideration.	
5)	Claim(s) is/are allowed.		
6)[	Claim(s) <u>1-17</u> is/are rejected.		
7)	Claim(s) is/are objected to.		
8)	Claim(s) are subject to restriction and	l/or election requirement.	
Applicati	on Papers		
9) 🗌 .	The specification is objected to by the Exami	ner.	
10)	The drawing(s) filed on is/are: a)☐ acc	cepted or b) objected to by	the Examiner.
<u> </u>	Applicant may not request that any objection to		
11) 🗌 🤄	The proposed drawing correction filed on		disapproved by the Examiner.
	If approved, corrected drawings are required in	•	
	The oath or declaration is objected to by the I	Examiner.	
Priority L	ınder 35 U.S.C. §§ 119 and 120		
13)	Acknowledgment is made of a claim for fore	ign priority under 35 U.S.C	. § 119(a)-(d) or (f).
a)[	☐ All b)☐ Some * c)☐ None of:		
	1. Certified copies of the priority docume	ints have been received.	
	2. Certified copies of the priority docume	ints have been received in	Application No
* S	3. Copies of the certified copies of the pr application from the International E See the attached detailed Office action for a li	Bureau (PCT Rule 17.2(a))	
	acknowledgment is made of a claim for dome	,	
а	) ☐ The translation of the foreign language p Acknowledgment is made of a claim for dome	provisional application has	been received.
Attachmen		, ,	
1) Notice 2) Notice	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449) Paper No(s	5) Notice o	v Summary (PTO-413) Paper No(s) If Informal Patent Application (PTO-152)

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### **DETAILED ACTION**

### Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Applicant's Admitted Prior Art (AAPA) in view of Tsuchiaki (U.S. 5,963,789)

Regarding claims 1, 9, 14, and 15, AAPA discloses in figure 1 a method of providing a heterojunction bipolar transistor structure comprising at least an underlying SiGe base region 22, an insulator layer 26 formed on surface portions of the underlying SiGe base region, and an emitter 28 formed on the insulator layer and in contact with the underlying SiGe base region through an emitter opening formed in the insulator layer, the emitter, the insulator layer and the SiGe base region each having exposed sidewalls; and siliciding exposed silicon surfaces of at least the emitter and the SiGe base region. AAPA does not disclose forming a passivation layer on the exposed sidewalls of the emitter, the insulator layer and portions of the SiGe base region.

Tsuchiaki discloses column 7, lines 1-9, that passivation layer 204 of figure 2C protects the sidewalls of the device shown. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to form passivation layer on exposed sidewalls of the emitter, the insulator layer, and portion of the base region to protect those layers, and further isolate the emitter and the base contacts.

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Regarding claims 2, and 5-8, Tsuchiaki does not expressly disclose passivation layer is formed by CVD. It would have been obvious to one of ordinary skill in the art at the time the invention was made to use CVD at the condition the applicant discloses, since it was known in the art CVD under those conditions is used to deposit layers in a semiconductor device.

Regarding claims 3, 4, 16, and 17, AAPA in view of Tsuchiaki discloses the claimed invention except for the passivation layer made of nitride, oxide, and oxynitride, or any combination thereof. It would have been obvious to one of ordinary skill in the art at the time the invention was made to use these materials as passivation layer since it was known in the art that these layers are used as passivation layer.

Regarding claims 10-12, AAPA discloses the claimed invention except insulation layer made of Sio<sub>2</sub> or Si oxynitride, silicon used in the substrate, and an intrinsic emitter. It would have been obvious to one of ordinary skill in the art at the time the invention was made to use these materials as passivation layer since it was known in the art that these materials are commonly used as insulator and substrate, and use intrinsic emitter so there would be no need for adding impurities to the emitter.

Regarding claim 13, AAPA discloses patterned insulator 26 of figure 1. AAPA does not disclose multiple patterned insulator layer. It would have been obvious to one of ordinary skill in the art at the time the invention was made to use multiple insulator layer since it has been held that mere duplication of the essential working parts of a device involves only routine skill in the art.

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## Response to Amendment

3. Applicant's arguments with respect to the pending claims have been considered but are most in view of the new ground(s) of rejection.

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dana Farahani whose telephone number is (703)305-1914. The examiner can normally be reached on M-F 9:00AM - 6:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (703)306-2794. The fax phone numbers for the organization where this application or proceeding is assigned are (703)872-9318 for regular communications and (703)872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703)308-0956.

Dana Farahani April 23, 2002

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